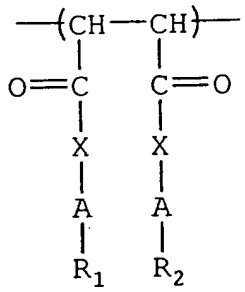
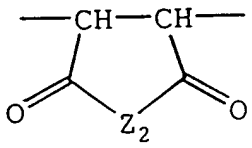
(B) a polymer having at least either a repeating unit represented by the following formula (Ia) or a repeating unit represented by the following formula (Ib) and a repeating unit represented by the following formula (II) and having a group capable of decomposing by the action of an acid, and

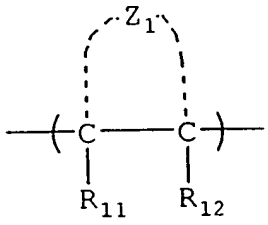
a1 (C) a compound capable of decomposing by the action of an acid to generate a sulfonic acid:



(Ia)



(Ib)



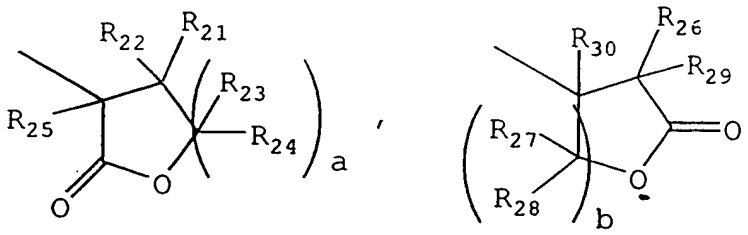
(II)

wherein

in formula (Ia), R_1 and R_2 each independently represents hydrogen atom, a cyano group, a hydroxyl group, -COOH, -$COOR_5$, -CO-NH-R_6, -CO-NH-SO_2-R_6 (wherein R_5 represents an alkyl group which may have a substituent, a cyclic hydrocarbon group which may have a substituent or a -Y group shown below, and

R_6 represents an alkyl group which may have a substituent or a cyclic hydrocarbon group which may have a substituent), an alkyl group which may be substituted, an alkoxy group which may be substituted, a cyclic hydrocarbon group which may be substituted or a -Y group shown below, X represents oxygen atom, sulfur atom, -NH-, $-NHSO_2-$ or $-NHSO_2NH-$, and A represents a single bond or a divalent linking group:

-Y group:



(wherein R_{21} to R_{30} each independently represents hydrogen atom or an alkyl group which may have a substituent, and a and b each represents 1 or 2);

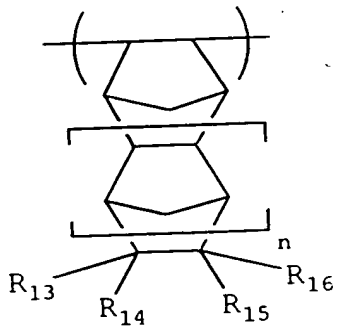
in formula (Ib), Z_2 represents -O- or $-N(R_3)-$ (wherein R_3 represents hydrogen atom, a hydroxyl group or $-OSO_2-R_4$ (wherein R_4 represents an alkyl group, a haloalkyl group, a cycloalkyl group or a camphor residue)); and

in formula (II), R_{11} and R_{12} each independently represents hydrogen atom, a cyano group, a halogen atom or an alkyl group which may have a substituent, and Z_1 represents an atomic group necessary for forming an alicyclic structure which

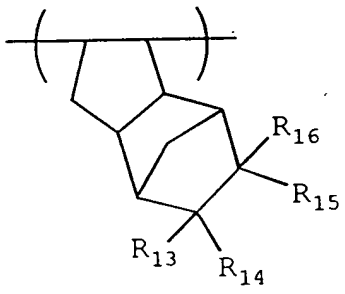
contains two bonded carbon atoms and may have a substituent.

2 (amended). The positive photoresist composition for far ultraviolet exposure as claimed in claim 1, wherein Z_1 in formula (II) represents an atomic group necessary for forming a bridged alicyclic structure which contains two bonded carbon atoms and may have a substituent.

3 (amended). The positive photoresist composition for far ultraviolet exposure as claimed in claim 1, wherein the repeating unit represented by formula (II) is that represented by the following formula (II-A) or (II-B):



(II-A)



(II-B)

wherein R_{13} to R_{16} each independently represents hydrogen atom, a halogen atom, a cyano group, -COOH, -$COOR_5$ (wherein R_5 is as defined in claim 1) , a group capable

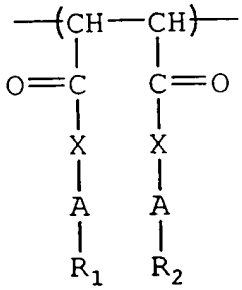
of decomposing by the action of an acid, -C(=O)-X-A-R_{17} (wherein X and A are as defined in claim 1, and R_{17} represents -COOH, -$COOR_5$, -CN, a hydroxyl group, an alkoxy group which may have a substituent, -CO-NH-R_6, -CO-NH-SO_2-R_6 (wherein R_5 and R_6 are as defined in claim 1) or a -Y group as defined in claim 1), an alkyl group which may have a substituent or a cyclic hydrocarbon group which may have a substituent, at least two of R_{13} to R_{16} may be combined to form a ring, and n represents 0 or 1.

4 (amended). A positive photoresist composition for far ultraviolet exposure, comprising:

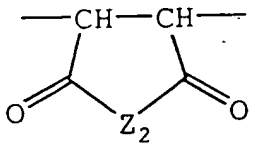
(A) a compound capable of generating an acid by the irradiation of an actinic ray or radiation,

(B) a polymer having at least either a repeating unit represented by the following formula (Ia) or a repeating unit represented by the following formula (Ib) and a repeating unit represented by the following formula (II) and having a group capable of decomposing by the action of an acid, and

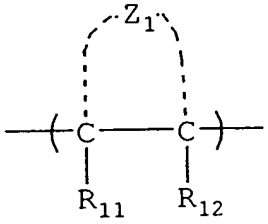
(D) a fluorine-type and/or silicon-type surface active agent:



(Ia)



(Ib)

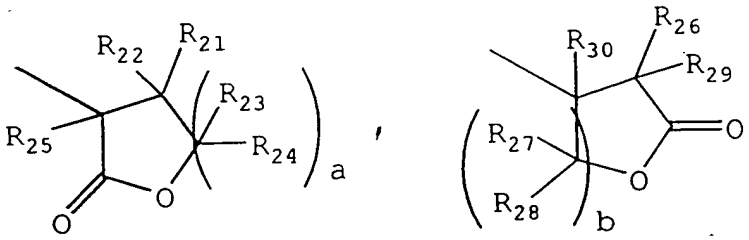


(II)

wherein

in formula (Ia), R_1 and R_2 each independently represents hydrogen atom, a cyano group, a hydroxyl group, -COOH, $-COOR_5$, -CO-NH-R_6, -CO-NH-SO_2-R_6 (wherein R_5 represents an alkyl group which may have a substituent, a cyclic hydrocarbon group which may have a substituent or a -Y group shown below, and R_6 represents an alkyl group which may have a substituent or a cyclic hydrocarbon group which may have a substituent), an alkyl group which may be substituted, an alkoxy group which may be substituted, a cyclic hydrocarbon group which may be substituted or a -Y group shown below, X represents oxygen atom, sulfur atom, -NH-, $-NHSO_2-$ or $-NHSO_2NH-$, and A represents a single bond or a divalent linking group:

-Y group:



(wherein R_{21} to R_{30} each independently represents hydrogen atom or an alkyl group which may have a substituent, and a and b each represents 1 or 2);

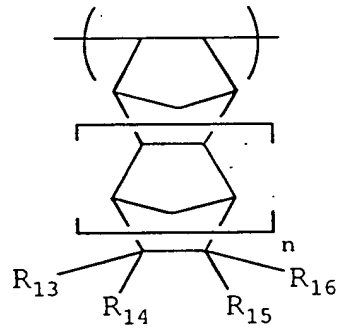
in formula (Ib), Z_2 represents -O- or -N(R_3)- (wherein R_3 represents hydrogen atom, a hydroxyl group or -OSO_2-R_4 (wherein R_4 represents an alkyl group, a haloalkyl group, a cycloalkyl group or a camphor residue)); and

in formula (II), R_{11} and R_{12} each independently represents hydrogen atom, a cyano group, a halogen atom or an alkyl group which may have a substituent, and Z_1 represents an atomic group necessary for forming an alicyclic structure which contains two bonded carbon atoms and may have a substituent.

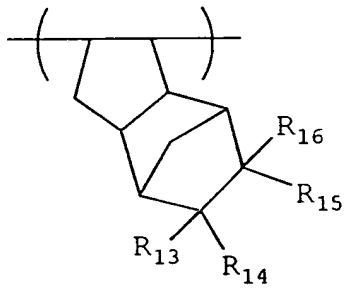
5 (amended). The positive photoresist composition for far ultraviolet exposure as claimed in claim 4, wherein Z_1 in formula (II) represents an atomic group necessary for forming a bridged alicyclic structure which contains two bonded carbon atoms and may have a substituent.

6 (amended). The positive photoresist composition for far ultraviolet

exposure as claimed in claim 4, wherein the repeating unit represented by formula (II) is that represented by the following formula (II-A) or (II-B):



(II-A)



(II-B)

wherein R_{13} to R_{16} each independently represents hydrogen atom, a halogen atom, a cyano group, -COOH, -$COOR_5$ (wherein R_5 is as defined in claim 4) , a group capable of decomposing by the action of an acid, -C(=O)-X-A-R_{17} (wherein X and A are as defined in claim 4, and R_{17} represents -COOR, -$COOR_5$, -CN, a hydroxyl group, an alkoxy group which may have a substituent, -CO-NH-R_6, -CO-NH-SO_2R_6 (wherein R_5 and R_6 are as defined in claim 4) or a -Y group as defined in claim 4), an alkyl group which may have a substituent or a cyclic hydrocarbon group which may have a substituent, at least two of R_{13} to R_{16} may be combined to form a ring, and n represents 0 or 1.

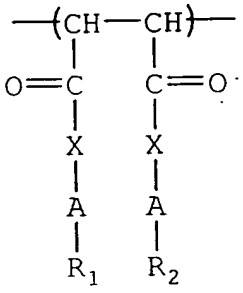
9 (amended). A positive photoresist composition for far ultraviolet exposure,

comprising:

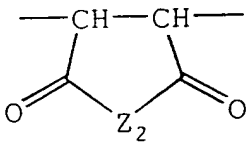
(A) a compound capable of generating an acid by the irradiation of an actinic ray or radiation,

(B) a polymer having at least either a repeating unit represented by the following formula (Ia) or a repeating unit represented by the following formula (Ib) and a repeating unit represented by the following formula (II) and having a group capable of decomposing by the action of an acid, and

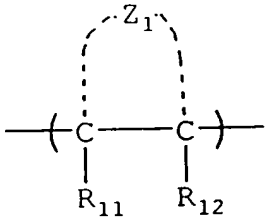
(E) a mixed solvent containing at least one selected from the group consisting of butyl acetate and propylene glycol monoalkyl ether carboxylate and at least one selected from the group consisting of ethyl lactate and propylene glycol monoalkyl ether:



(Ia)



(Ib)

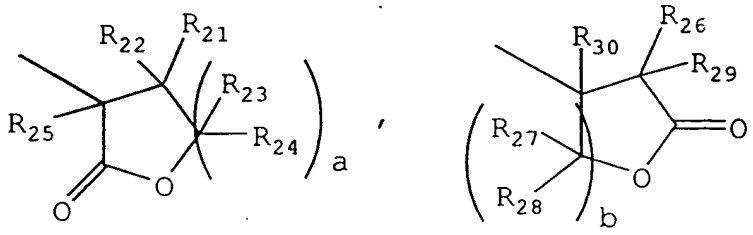


(II)

wherein

in formula (Ia), R_1 and R_2 each independently represents hydrogen atom, a cyano group, a hydroxyl group, -COOH, -$COOR_5$, -CO-NH-R_6, -CO-NH-SO_2-R_6 (wherein R_5 represents an alkyl group which may have a substituent, a cyclic hydrocarbon group which may have a substituent or a -Y group shown below, and R_6 represents an alkyl group which may have a substituent or a cyclic hydrocarbon group which may have a substituent), an alkyl group which may be substituted, an alkoxy group which may be substituted, a cyclic hydrocarbon group which may be substituted or a -Y group shown below, X represents oxygen atom, sulfur atom, -NH-, -$NHSO_2$- or -$NHSO_2NH$-, and A represents a single bond or a divalent linking group:

-Y group:



(wherein R_{21} to R_{30} each independently represents hydrogen atom or an alkyl group which may have a substituent, and a and b each represents 1 or 2);

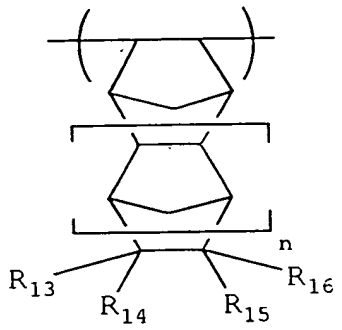
in formula (Ib) , Z_2 represents -O- or -N(R_3)- (wherein R_3 represents hydrogen atom, a hydroxyl group or -OSO_2-R_4 (wherein R_4 represents an alkyl group, a

haloalkyl group, a cycloalkyl group or a camphor residue)); and

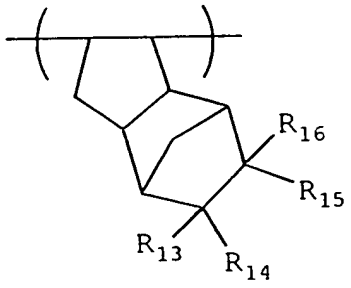
in formula (II), R_{11} and R_{12} each independently represents hydrogen atom, a cyano group, a halogen atom or an alkyl group which may have a substituent, and Z_1 represents an atomic group necessary for forming an alicyclic structure which contains the two bonded carbon atoms and may have a substituent.

10 (amended). The positive photoresist composition for far ultraviolet exposure as claimed in claim 9, wherein Z_1 in formula (II) represent an atomic group necessary for forming a bridged alicyclic structure which contains two bonded carbon atoms and may have a substituent.

11 (amended). The positive photoresist composition for far ultraviolet exposure as claimed in claim 9, wherein the repeating unit represented by formula (II) is that represented by the following formula (II-A) or (II-B):



(II-A)



(II-B)

wherein R_{13} to R_{16} each independently represents hydrogen atom, a halogen atom, a cyano group, -COOH, -$COOR_5$ (wherein R_5 is as defined in claim 9), a group capable of decomposing by the action of an acid, -C(=O)-X-A-R_{17} (wherein X and A are as defined in claim 9, and R_{17} represents -COOH, -$COOR_5$, -CN, a hydroxyl group, an alkoxy group which may have a substituent, -CO-NH-R_6, -CO-NH-SO_2-R_6 (wherein R_5 and R_6 are as defined in claim 1) or a -Y group as defined in claim 9), an alkyl group which may have a substituent or a cyclic hydrocarbon group which may have a substituent, at least two of R_{13} to R_{16} may be combined to form a ring, and n represents 0 or 1.